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APPLICATION NO.	F	TLING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/687,573	10/687,573 10/15/2003		Edward J. Seppi	7129	
23639	7590	09/26/2006		EXAM	INER
	•	TCHEN LLP	YUN, JURIE		
18 FLOOR	IBAKCAL	DERO CENTER	ART UNIT	PAPER NUMBER	
SAN FRAN	ICISCO,	CA 94111-4067	2882		
				DATE MAILED: 09/26/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)		
		10/687,573	SEPPI ET AL.		
	Office Action Summary	Examiner	Art Unit		
		Jurie Yun	2882		
Period fo	The MAILING DATE of this communication ap or Reply	pears on the cover sheet with the	e correspondence address		
WHI(- Exte after - If NO - Failu Any	ORTENED STATUTORY PERIOD FOR REPL CHEVER IS LONGER, FROM THE MAILING D nsions of time may be available under the provisions of 37 CFR 1. SIX (6) MONTHS from the mailing date of this communication.) by (6) MONTHS from the mailing date of this communication.) or priod for reply is specified above, the maximum statutory period are to reply within the set or extended period for reply will, by statut reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICATE 136(a). In no event, however, may a reply be will apply and will expire SIX (6) MONTHS free, cause the application to become ABANDO	ON. timely filed om the mailing date of this communication. NED (35 U.S.C. § 133).		
Status					
1)⊠ 2a)□ 3)□	Responsive to communication(s) filed on 30 A This action is FINAL . 2b) This Since this application is in condition for allower closed in accordance with the practice under	s action is non-final. ance except for formal matters, p			
Disposit	ion of Claims				
5)□ 6)⊠ 7)□ 8)□ Applicat i	Claim(s) 1-3,6-13,21-25,27-34 and 39-53 is/a 4a) Of the above claim(s) is/are withdra Claim(s) is/are allowed. Claim(s) 1-3,6-13,21-25,27-34 and 39-53 is/a Claim(s) is/are objected to. Claim(s) are subject to restriction and/o ion Papers The specification is objected to by the Examine The drawing(s) filed on 11 May 2006 is/are: a	ewn from consideration. The rejected. The rejection requirement. The rejection requirement.	o by the Evaminer		
	Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the E	e drawing(s) be held in abeyance. Setion is required if the drawing(s) is	See 37 CFR 1.85(a). objected to. See 37 CFR 1.121(d).		
Priority ι	ınder 35 U.S.C. § 119				
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 					
Attachmen [,]	((s)				
1) Notic 2) Notic 3) Inforr	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO/SB/08) r No(s)/Mail Date	4) Interview Summa Paper No(s)/Mail 5) Notice of Informa 6) Other:	Date		

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DETAILED ACTION

Continued Examination Under 37 CFR 1.114

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 8/30/06 has been entered.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 1-3, 6-13, 21-25, 27-34, 39-42, and 46-53 are rejected under 35 U.S.C. 103(a) as being unpatentable over Besson (USPN 6,950,493 B2).
- 4. With respect to claims 1, 21, and 39, Besson discloses an apparatus for use in a radiation procedure, comprising: a radiation filter (Fig. 2, 150) having a first portion (152) and a second portion (154), the first and the second portions forming a layer for filtering radiation impinging thereon; wherein the first portion is made from a first X-ray filtering material, and the second portion is made from a second X-ray filtering material (column 9, lines 45-60 & column 11, lines 21-28); a structure (112) having a cavity, the radiation filter (150) in operative association with the structure (via control unit, 110); and a disk

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located within the cavity, the disk having a first target material and a second target material (column 21, lines 52-57). The first and the second filter factor is applied automatically using a machine (control unit, 110 controls motor, 156). Besson does not specifically disclose the first target material corresponds with the first portion of the radiation filter, and the second target material corresponds with the second portion of the radiation filter. Besson does imply this, however, at column 47, lines 11-38. It would have been obvious to one of ordinary skill in the art at the time the invention was made that this is done by Besson, to produce the desired spectrum, depending on the application being done, to obtain optimal imaging results. All X-ray system applications which include a filter take into account the target material which is being used, which determines the wavelength of X-rays generated, and the type of filter being used, to obtain the desired spectrum, which would be determined by the application being done, to obtain the best imaging results possible.

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- 5. With respect to claim 2, Besson discloses the first and the second target materials (Fig. 28A, 2702 & 2704) are part of a radiation source (Fig. 28B, 2802), and the apparatus further comprises the radiation source.
- 6. With respect to claim 3, Besson discloses a gantry to which the radiation source is secured (column 3, lines 53-54).
- 7. With respect to claim 6, Besson discloses the radiation source comprises an anode that includes a rare earth element, a platinum group metal, or combination thereof (column 21, lines 52-57).

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8. With respect to claim 7, Besson discloses the radiation source comprises a voltage generator (column 13, lines 59-60).

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- 9. With respect to claim 8, Besson discloses a switching element coupled to the voltage generator, the switching element configured to modulate the voltage generated by the voltage generator (column 35, lines 66+).
- 10. With respect to claim 9, Besson discloses an imager (114) for generating image data in response to radiation that has been filtered by the layer.
- 11. With respect to claims 10 and 29-33, Besson discloses the imager has a first image element for generating a first image data in response to radiation that has been filtered by the first portion of the radiation filter, and a second image element for generating a second image data in response to radiation that has been filtered by the second portion of the radiation filter (column 4, lines 39-64).
- 12. With respect to claim 11, Besson discloses a gantry, wherein the imager and the radiation filter are secured to the gantry (column 3, lines 53-54).
- 13. With respect to claim 12, Besson discloses the imager (114) is coupled to a support structure (128) for supporting an object (116) to which filtered radiation (132) is directed.
- 14. With respect to claims 13, 34, and 42, Besson discloses either or both of the first and second X-ray filtering materials are selected from the group consisting of aluminum, copper, and molybdenum (column 21, Table 1).

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15. With respect to claims 22 and 23, Besson discloses the first filter factor is applied by placing a first filter into the X-ray radiation, and the second filter factor is applied by

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placing a second filter into the X-ray radiation (column 9, lines 45-60).

16. With respect to claim 24, Besson discloses the first filter factor has a same filtering characteristic as the second filter factor (column 9, lines 45-60).

- 17. With respect to claim 25, Besson discloses the first filter factor is different from the second filter factor (column 9, lines 45-60).
- 18. With respect to claim 27, Besson discloses the first filter factor and the second filter factor are applied by placing a first filter and a second filter, respectively, into the first and second X-ray radiation (column 9, lines 45-60 & column 47, lines 11-38).
- 19. With respect to claims 28 and 40, Besson discloses the first filter (Fig. 2, 152) and the second filter (154) are secured to a rotatable structure (filter 150 is wheel-shaped and rotates).
- 20. With respect to claim 41, Besson discloses the positioner comprises a motor (156).
- 21. With respect to claim 46, Besson discloses an electron gun (Fig. 26, 2604) for sending electrons (2606) towards the first or the second target material (2608).
- 22. With respect to claims 47-50, Besson discloses an electron deflector for changing a path of the electrons; wherein the electron deflector comprises an electromagnetic field generator; wherein the electron deflector comprises a magnetic field generator; wherein the electron deflector physically deflects the electrons (column 45, lines 55+).

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- 23. With respect to claim 51, Besson discloses a gantry to which the structure is secured (column 3, lines 53-54).
- 24. With respect to claims 52 and 53, Besson discloses the structure is part of a MRI (column 60, line 6) or PET machine (column 59, lines 61-62).
- 25. Claims 43-45 are rejected under 35 U.S.C. 103(a) as being unpatentable over Besson (USPN 6,950,493 B2) as applied to claim 1 above, and further in view of Seki et al. (USPN 3,610,984).
- 26. With respect to claims 43-45, Besson does not specifically disclose the first target material forms a ring configuration; the first target material and the second target material are positioned concentrically relative to each other; and the first target material and the second target material are positioned relative to each other in a side-by-side configuration. Seki et al. disclose the first target material forms a ring configuration; the first target material and the second target material are positioned concentrically relative to each other (column 3, line 33); and the first target material and the second target material are positioned relative to each other in a side-by-side configuration (see Figs. 3-7). It would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the first and second target materials of Besson to form a ring configuration, wherein the first target material and the second target material are positioned concentrically relative to each other; and the first target material and the second target material are positioned relative to each other in a side-by-side

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configuration, to form a more compact anode, resulting in a smaller and lighter X-ray source.

Response to Arguments

27. Applicant's arguments with respect to the claims have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

28. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jurie Yun whose telephone number is 571 272-2497. The examiner can normally be reached on Monday-Friday 8:30-5:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Ed Glick can be reached on 571 272-2490. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

September 15, 2006